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**Amano et al.**

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(54) **LIQUID DISCHARGE NOZZLE FOR SEMICONDUCTOR SUBSTRATE PROCESSING APPARATUS**

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(\*) Notice: This patent is subject to a terminal disclaimer.

(\*\*) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (13) Cl.** ..... **23-01**

(52) **U.S. Cl.**  
USPC ..... **D23/213; D23/259**

(58) **Field of Classification Search**

USPC ..... D23/213, 214, 215, 223, 224, 226, 229,  
D23/230, 249, 259, 262; D15/135

CPC ..... A61H 9/0021; A61H 33/00; B05B 1/00;  
B05B 1/14; B05B 1/185; B05B 1/08;  
B05B 1/02; B05B 1/26; B05B 12/002;  
B05B 1/18; B05B 9/01

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a liquid discharge nozzle for semiconductor substrate processing apparatus, as shown and described herein.

**DESCRIPTION**

FIG. 1 a front, top perspective view of a liquid discharge nozzle for semiconductor substrate processing apparatus; FIG. 2 is a front elevational view thereof; FIG. 3 is a rear elevational view thereof; FIG. 4 is a left-side elevational view thereof; FIG. 5 is a right-side elevational view thereof; FIG. 6 is a top plan view thereof; and, FIG. 7 is a bottom plan view thereof.

**1 Claim, 7 Drawing Sheets**

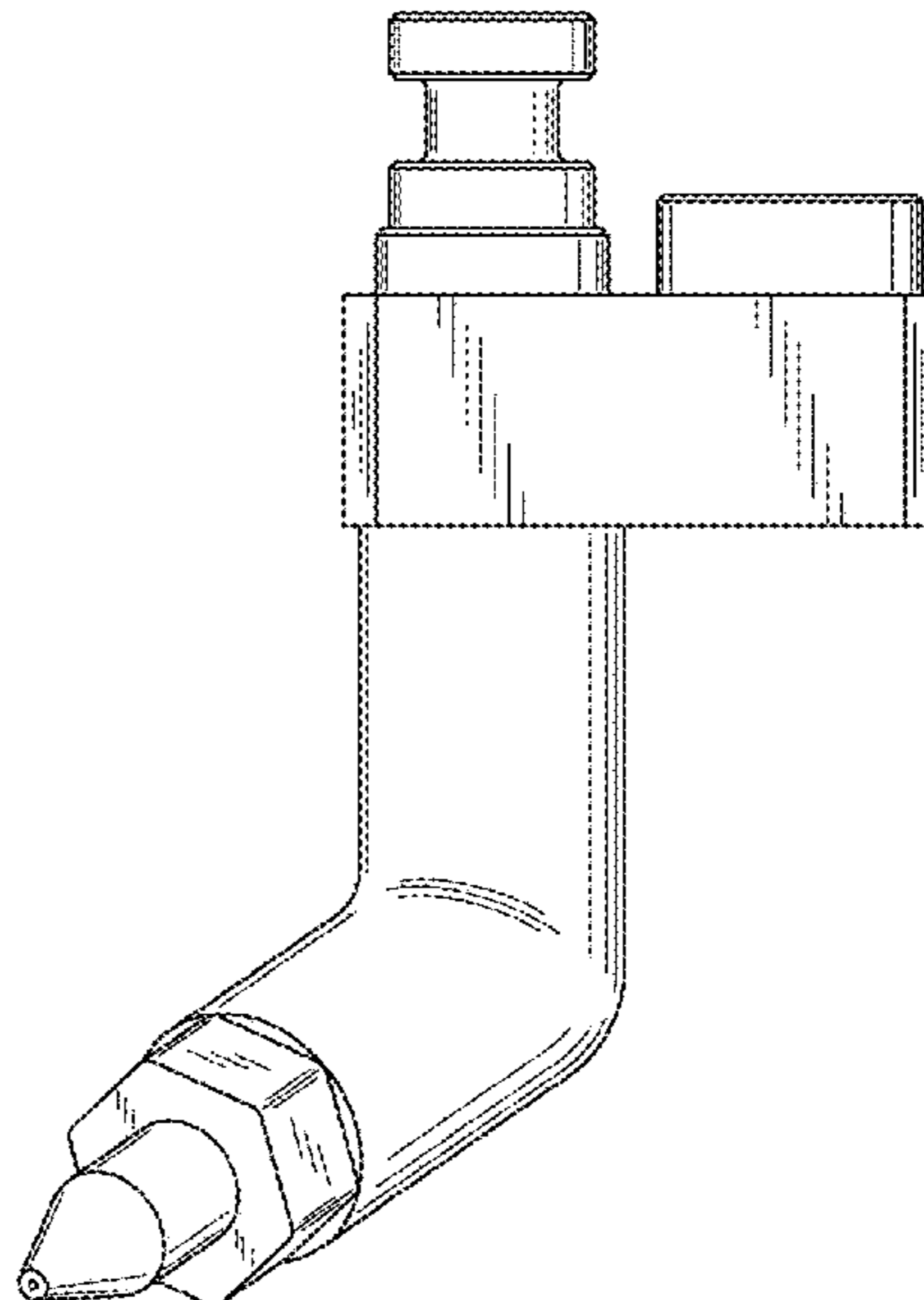
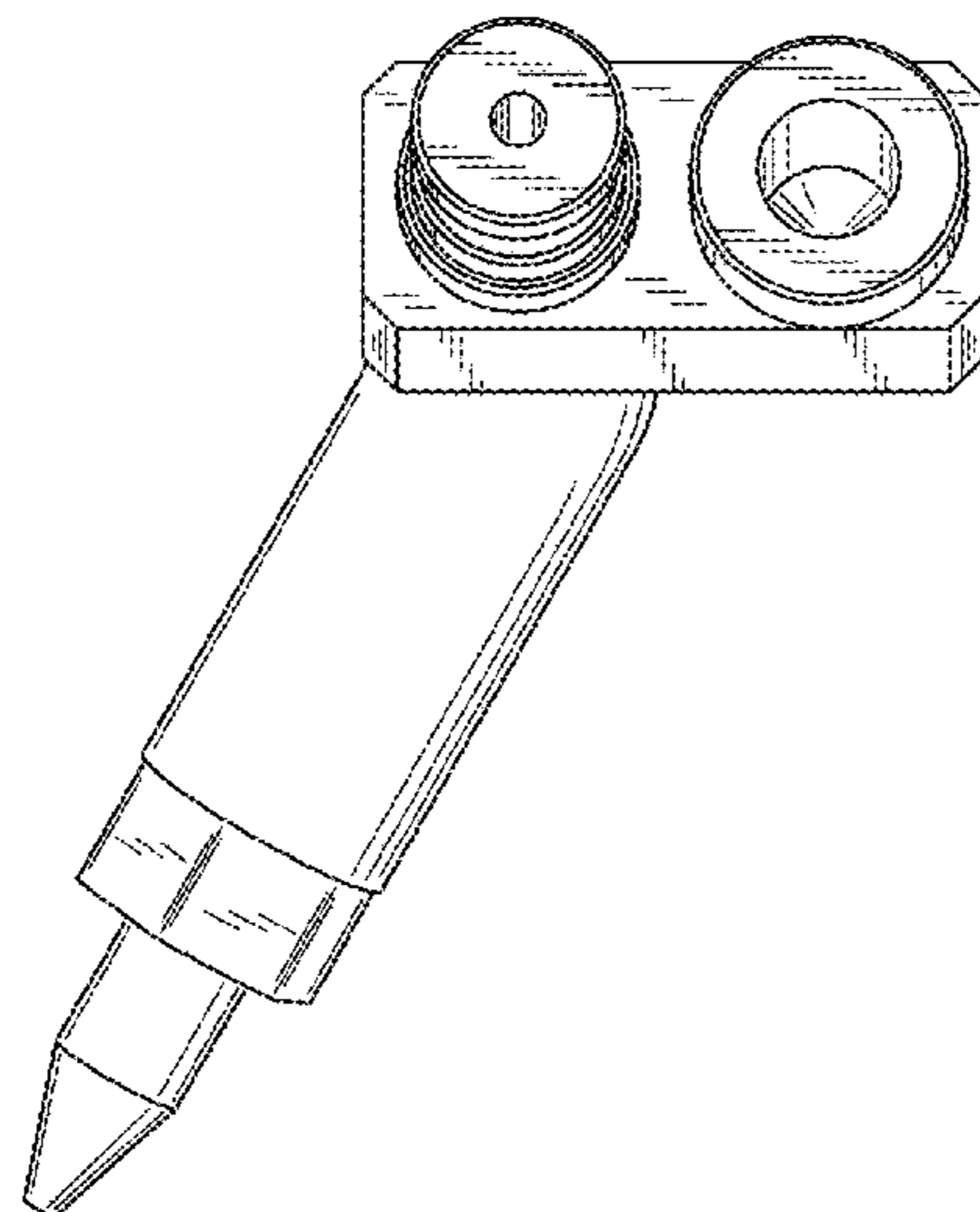


FIG. 1

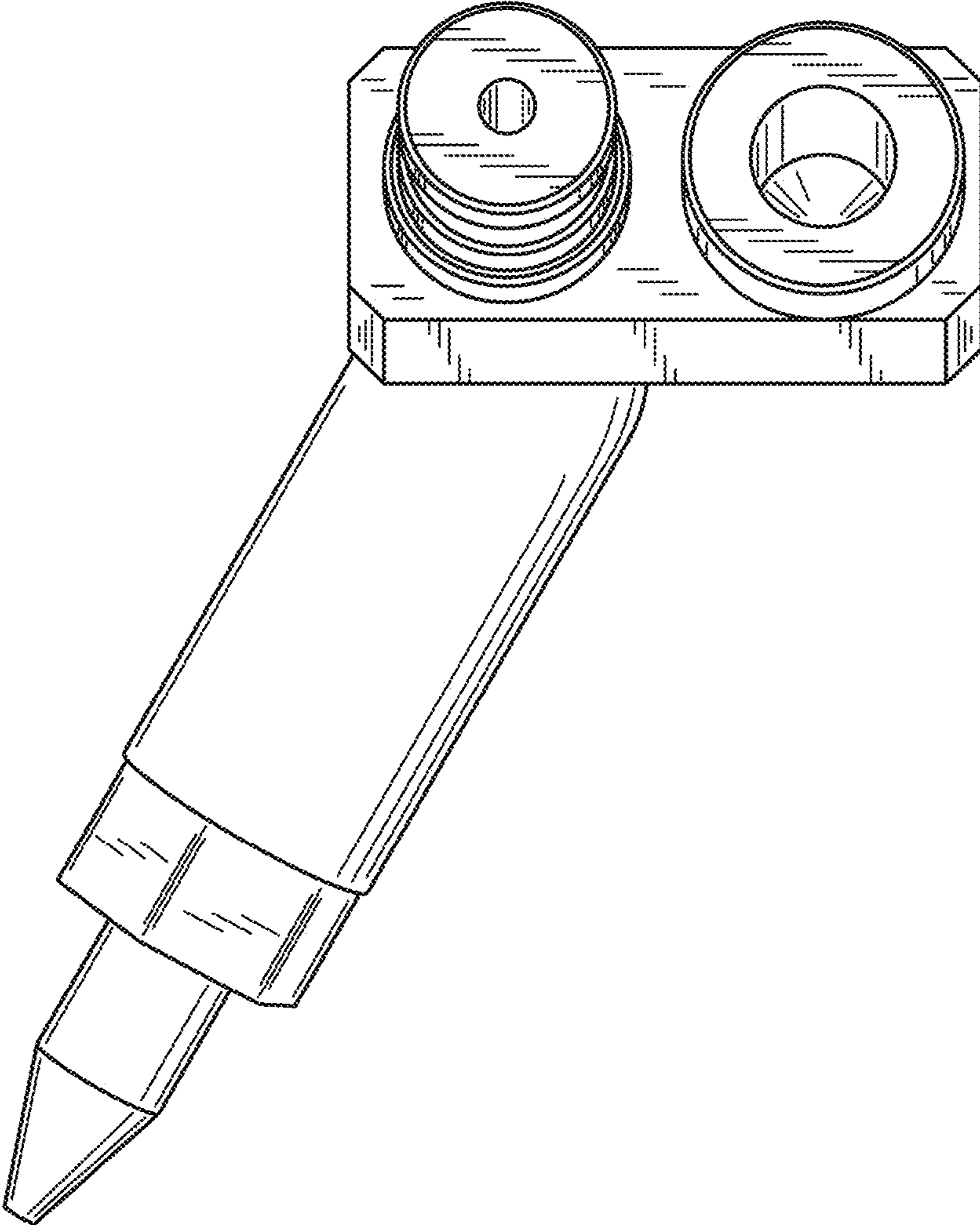
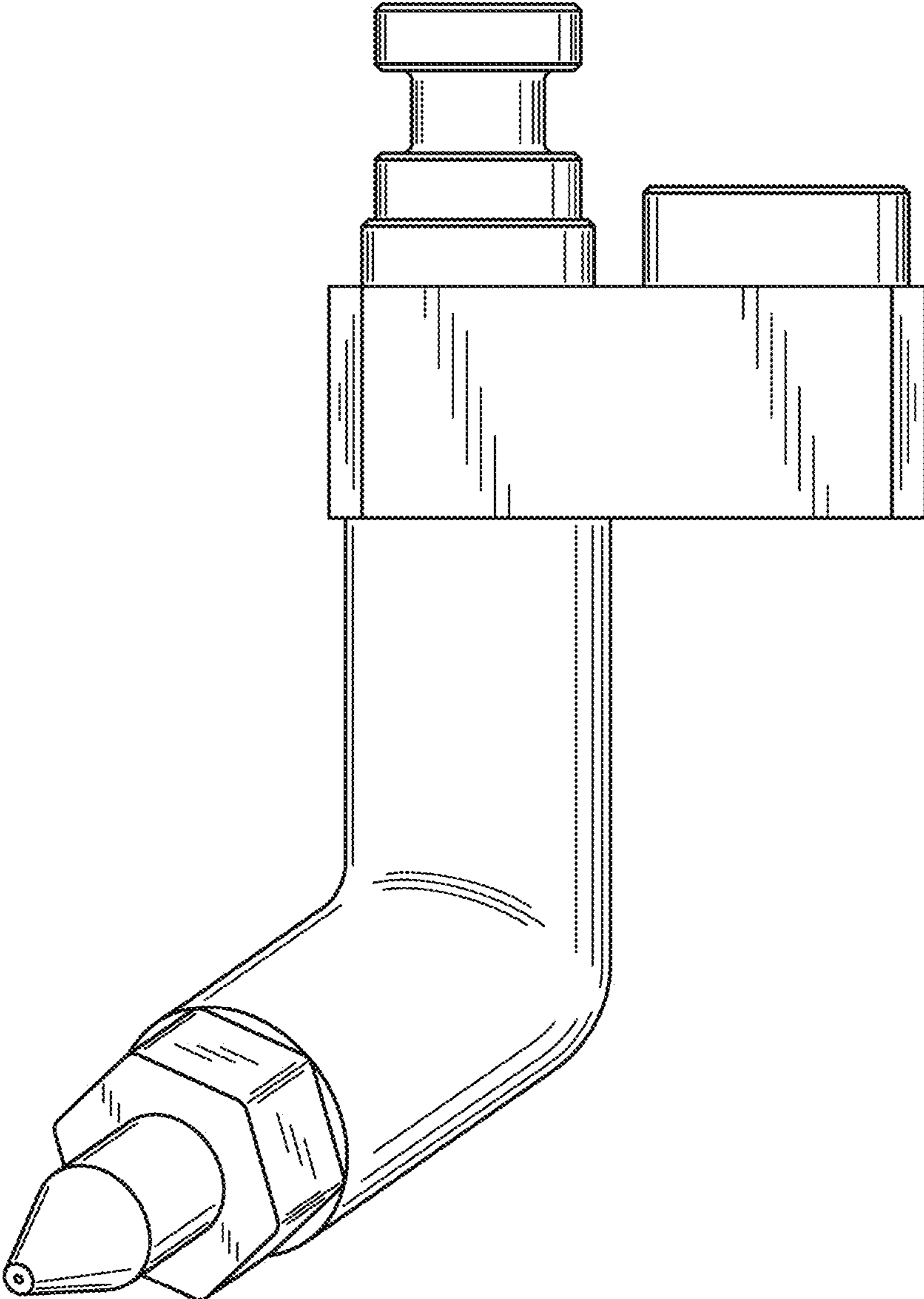


FIG. 2



*FIG. 3*

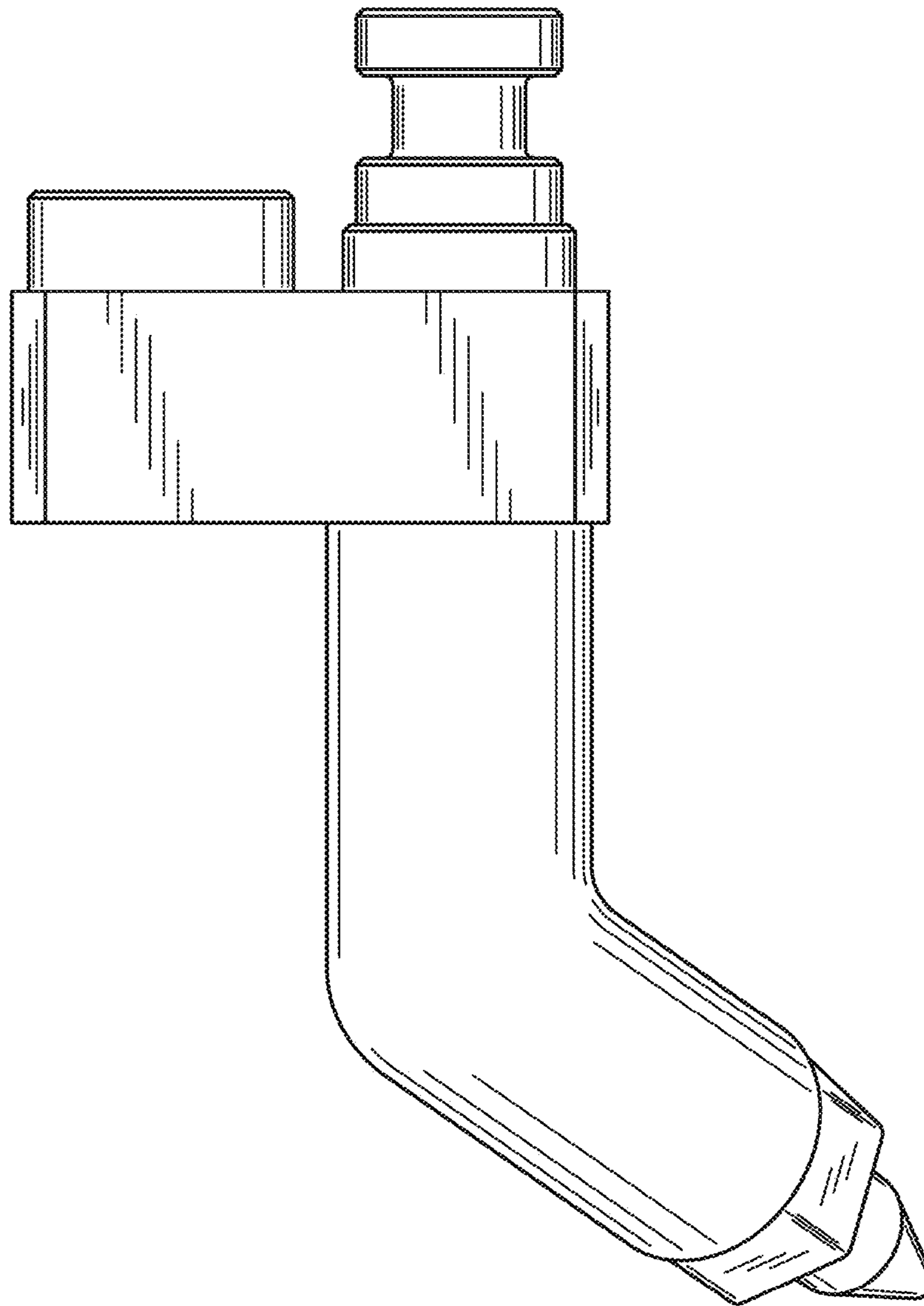
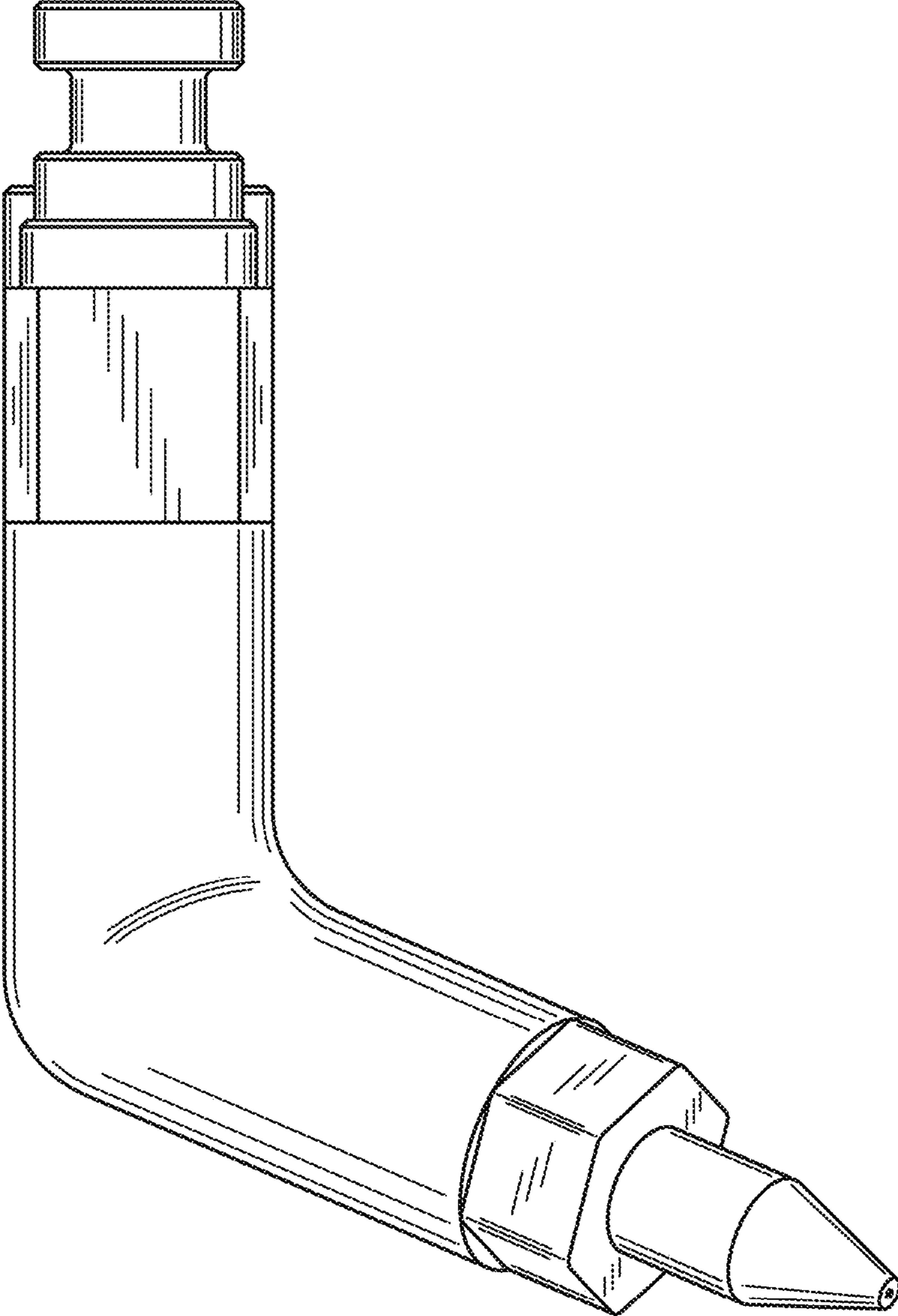


FIG. 4



*FIG. 5*

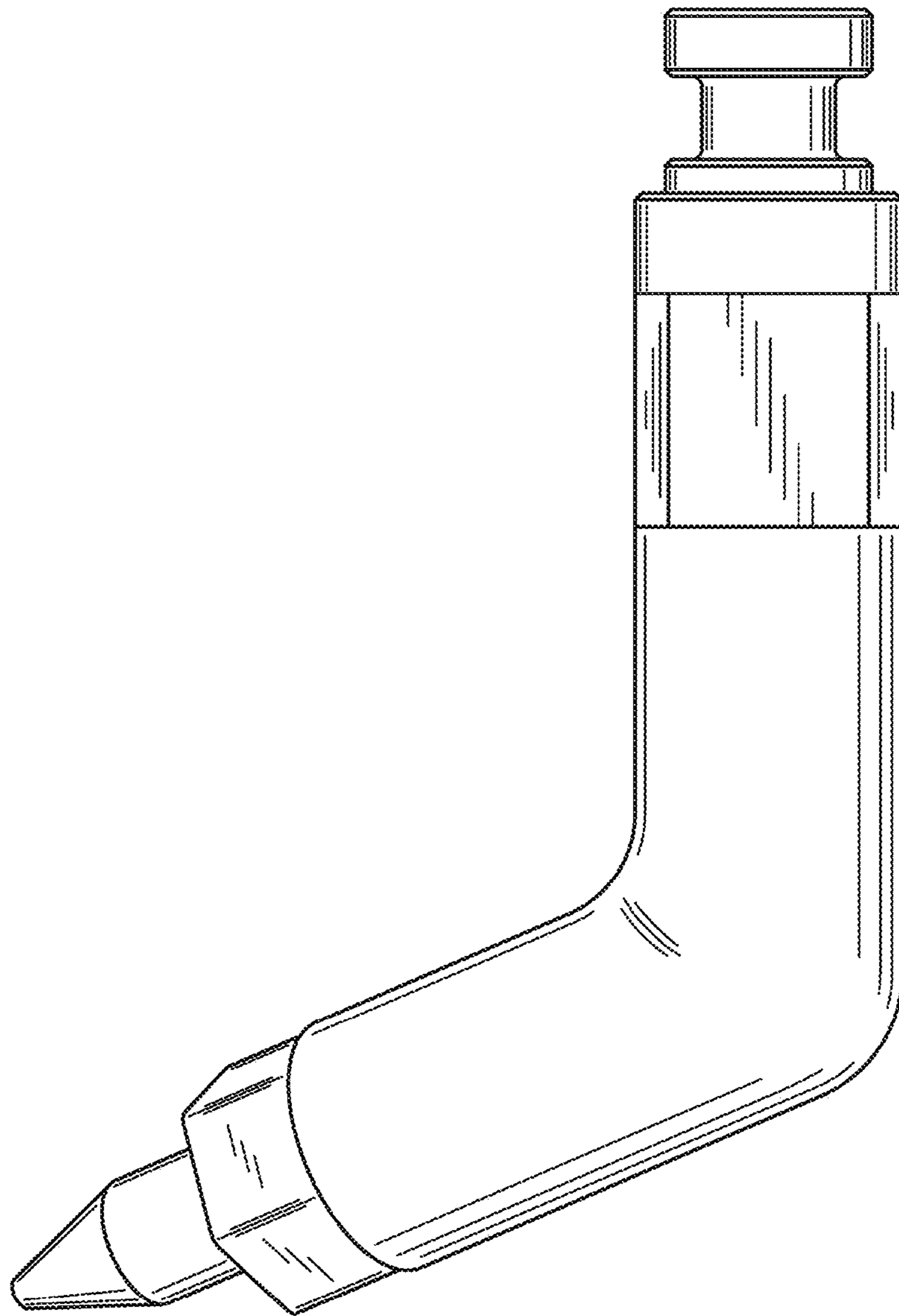
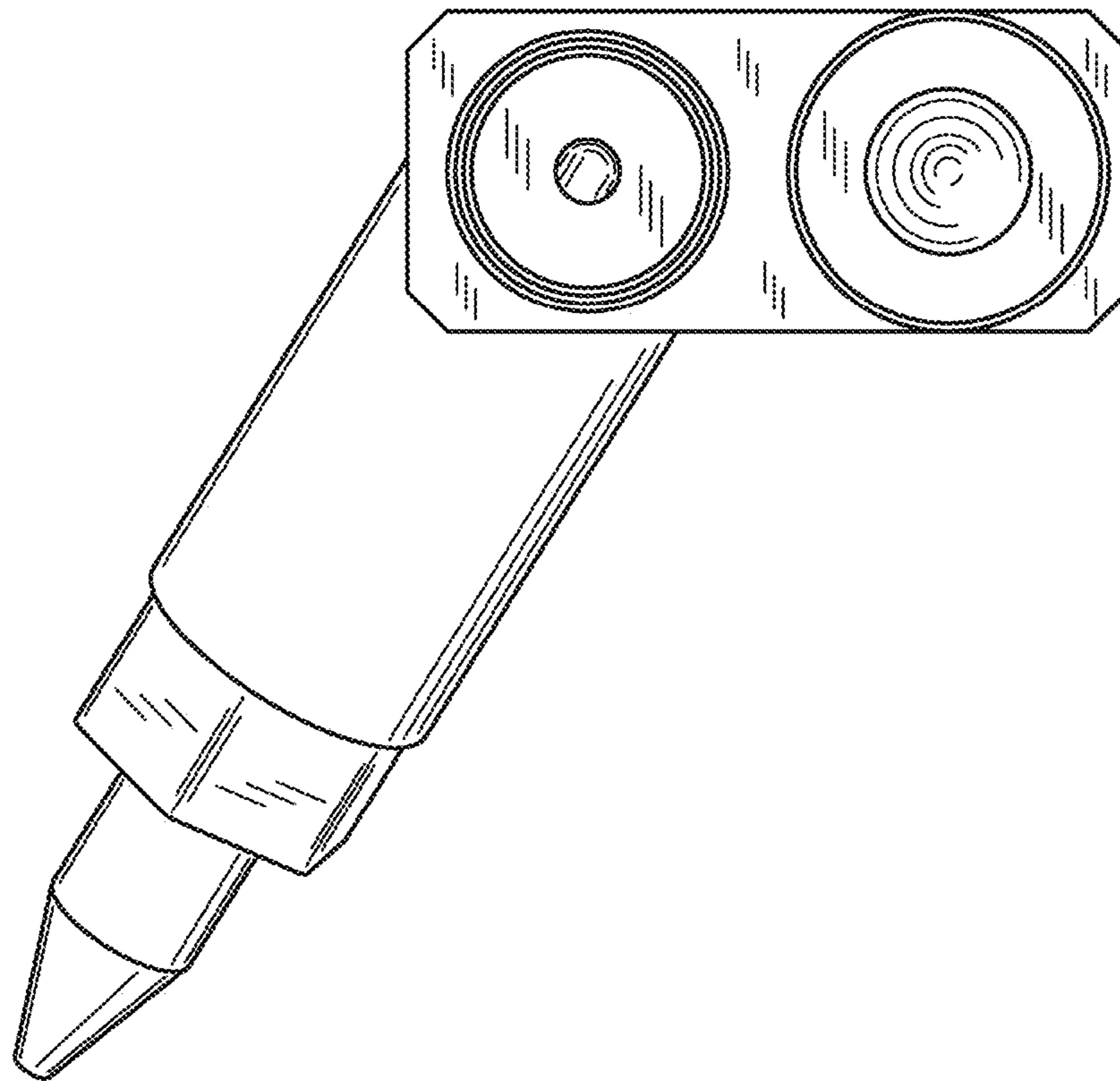


FIG. 6



*FIG. 7*

